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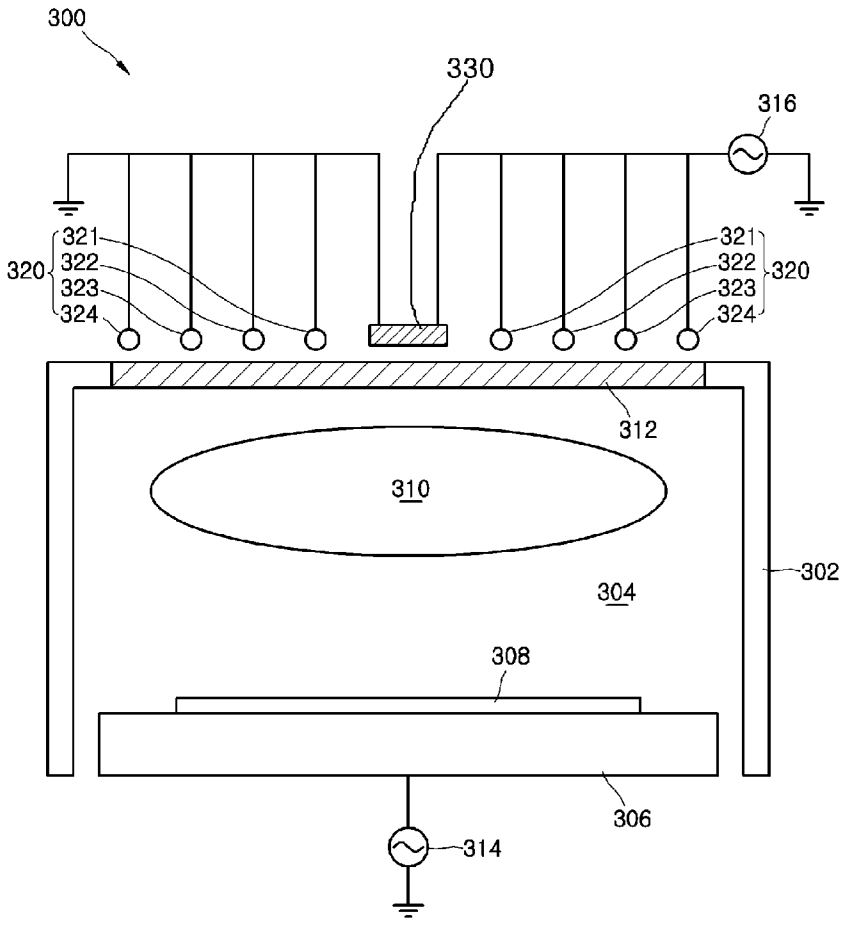
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(54) Title: PLASMA SOURCE COIL AND PLASMA CHAMBER USING THE SAME



(57) Abstract: A plasma source coil includes a bushing arranged at a center part, and a plurality of unit coils arranged in the form of a concentric circle from a circumference of the bushing on the bases of the bushing. One end of each unit coil and one end of the bushing are commonly connected to a power-supply terminal, and the other end of each unit coil and the other end of the bushing are commonly connected to a ground terminal.

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